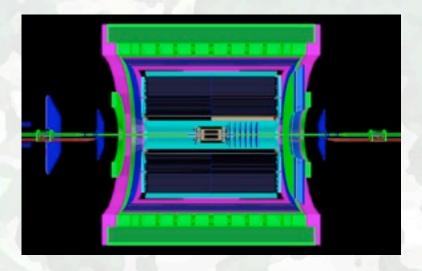


The STAR Forward GEM Tracker (FGT)

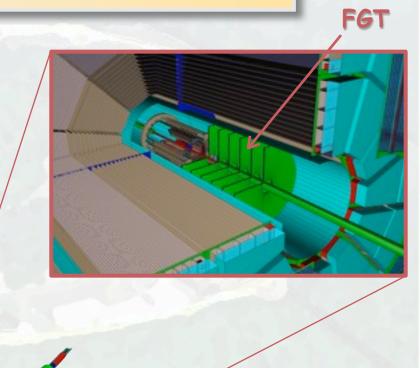
Bernd Surrow





Outline

- □ FGT Physics motivation W program
- FGT Layout Simulation results and optimization
- □ FGT Technical Realization
 - Triple-GEM detector development R&D
 - Mechanical design
 - Front-End Electronics
 - O DAQ
- ☐ FGT Schedule / Milestones
- Summary

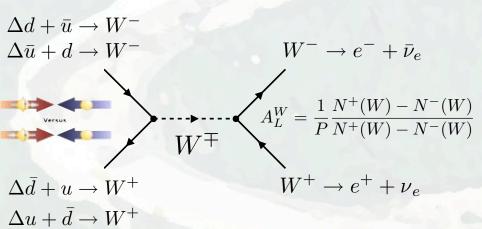




FGT Physics motivation - W program

Quark / Anti-Quark Polarization - W production

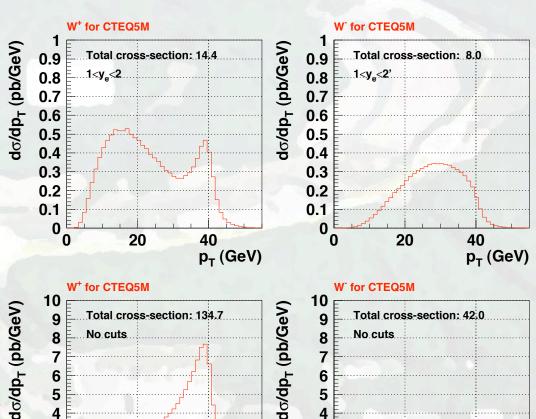
RHICBOS W simulation at 500GeV CME

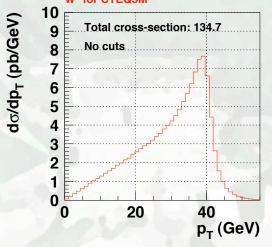


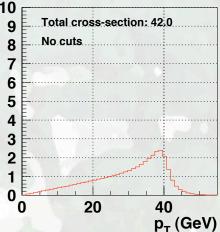
Key signature: High p_T lepton (e⁻/e⁺ or μ^{-}/μ^{+}) (Max. M_W/2) - Selection of W⁻/W⁺: Charge sign discrimination of

high p_T lepton

Required: Lepton/Hadron discrimination



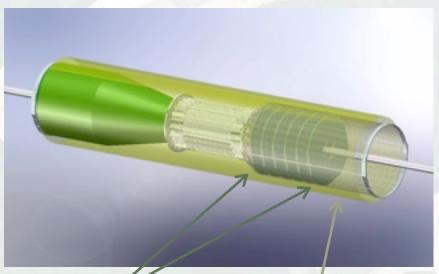






FGT Layout - Simulation results and optimization

Layout



FGT: 6 light-weight triple-GEM disks - WEST side of STAR

 New mechanical support structure

FGT



- □ SBIR proposal (1)
 - O SBIR: Small Business Innovation Research: US Government (DOE) funded program
 - ☑ Phase I: Explore feasibility of innovative concepts with award of up to \$100k
 - ☑ Phase II: Principal R&D effort with award of up to \$750k
 - ☐ Phase III: Commercial application
 - O SBIR: Collaborative effort of Tech-Etch Inc. with BNL, MIT and Yale

University - Production of GEM foils

- Develop optimized production process for small (10cm X 10cm) and larger GEM foils
- \square Investigate a variety of materials
- □ Study post production handling: Cleaning, surface treatment and storage
- O New SBIR proposal (submitted to DOE): 2D readout board using chemical etching



- □ SBIR proposal (2)
 - O Tech-Etch Inc.: Company profile
 - ☐ Manufacturer of precision flexible circuits
 - □ Extensive experience in etching of copper traces and polyamide
 - ☐ Strong ties to BNL, MIT and Yale University

Tech-Etch Inc.

O Critical performance parameters

- Achievable gain, gain uniformity and gain stability
- ☐ Energy resolution



http://www.tech-etch.com

O Status

- □ Phase I / II approved Dedicated production facility at Tech-Etch Inc.
- □ Success with 10cm X 10cm samples / First large GEM foils received



R&D Development at MIT

O Resources

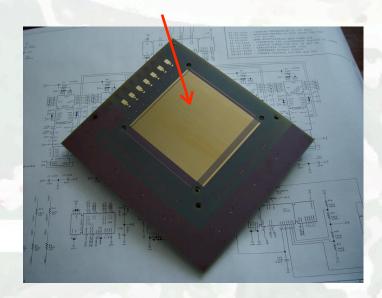
- □ 2 dedicated clean rooms (Class ~1000) (MIT Bates Laboratory / MIT Laboratory for Nuclear Science)
- □ HV radioactive source setup / HV box / Light-microscope / Laminar flow hood / GEM foil CCD camera scanner

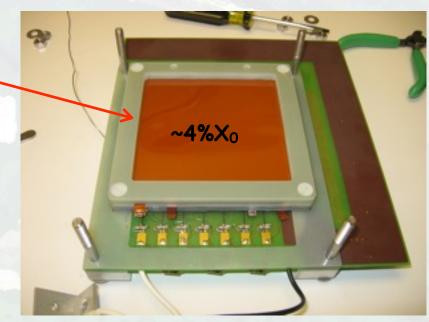
O Activities based on 10cm X 10cm samples

- □ Dark current / resistivity tests
- Optical scans
- Sources tests and test beam experiment at FNAL
- Publications: 1) U. Becker et al., NIM A556 527 (2006). 2) F. Simon et al., IEEE Trans. Nucl.
 Sci. 54, 2646 (2007). 3) F. Simon et al., NIM A598 432 (2009).



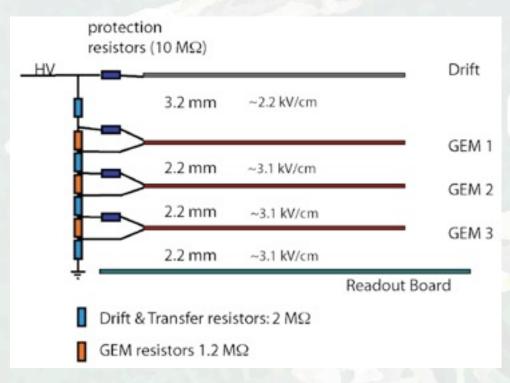
- Prototype triple-GEM configuration (1)
 - O Prototype triple-GEM detector (Ar/CO₂
 70:30 gas-mixture) to allow flexible handling
 - O Integrated APV25-S1 chip readout system
 - 2D projective readout board, using laser etching and micro-machining

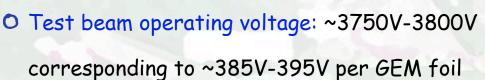




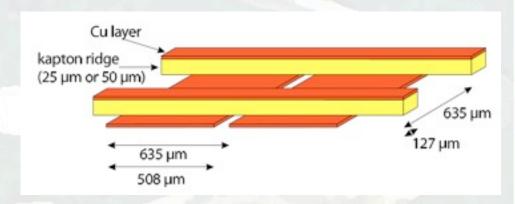


Prototype triple-GEM configuration (2)





O Testbeam effective gain: ~3.5·10³ (~2.5·10⁴ bench tests)



- O Laser etched 2D readout board (Compunetics Inc.)
- O Test beam configuration:

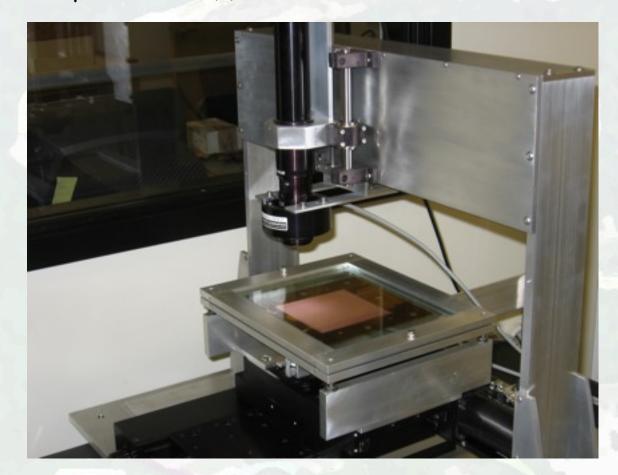
Top strips (Y): ~127µm

Bottom strips (X): 508µm

O Two separations: 25µm and 50µm

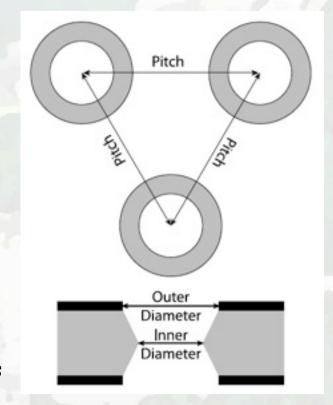


Optical scans (1)



- Check for defects:
 - Missing holes, enlarged holes, dirt in holes and etching defects

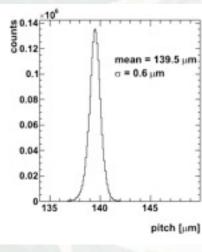
- O 2D scanning table with CCD camera fully automated
- Scan GEM foils to measure hole diameter (inner and outer) and pitch

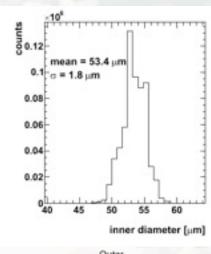


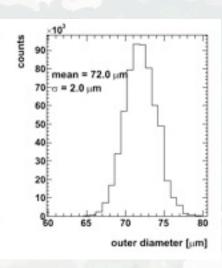


Optical scans (2)

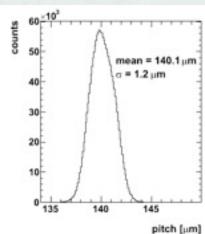
Tech-Etch

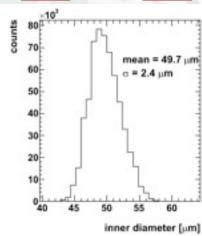


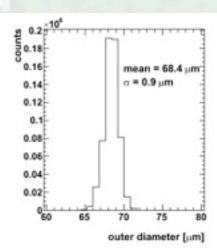










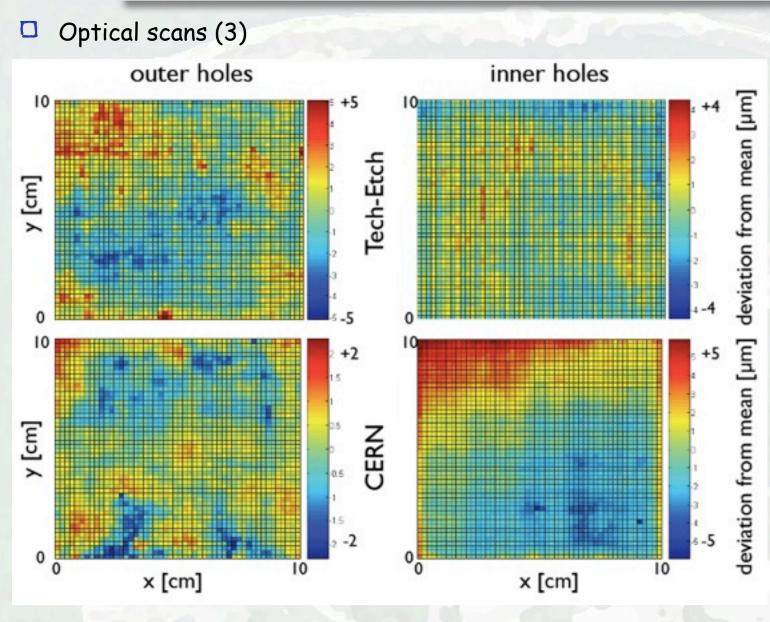


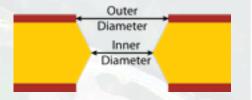
parameters
are similar
for TechEtch and
CERN foils

(10cm X 10cm

samples)







Uniformityof outer/

inner hole

diameters

for Tech-

Etch and

CERN foils

(10cm X 10cm

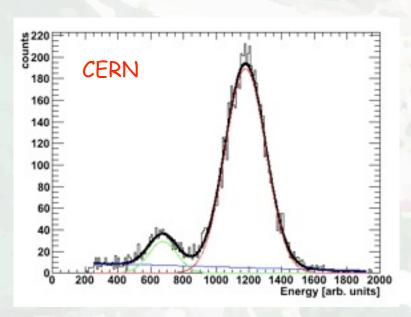
samples)

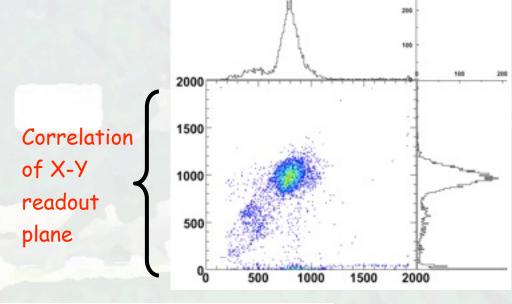


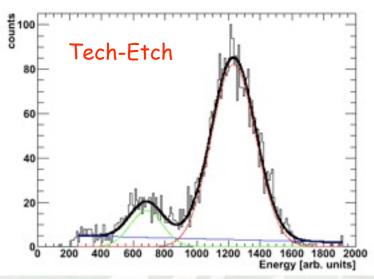
GEM foil test results

□ Source tests (1)

- Two identical detectors, one with CERN foils, one using Tech-Etch foils
- Doth detectors give reasonable X-Ray spectrum using ⁵⁵Fe source with comparable energy resolution (~20%)

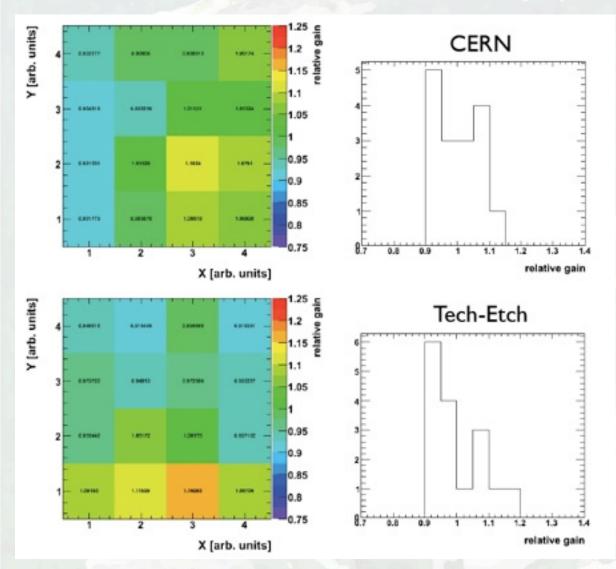








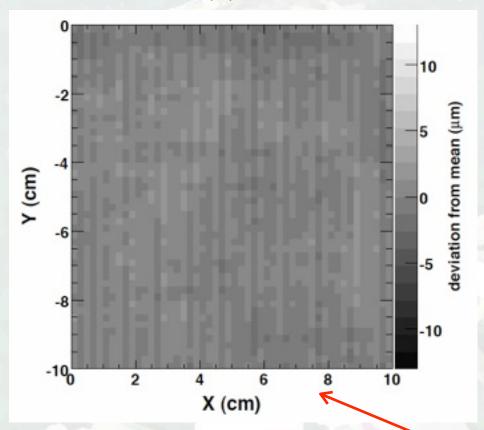
□ Source tests (2)

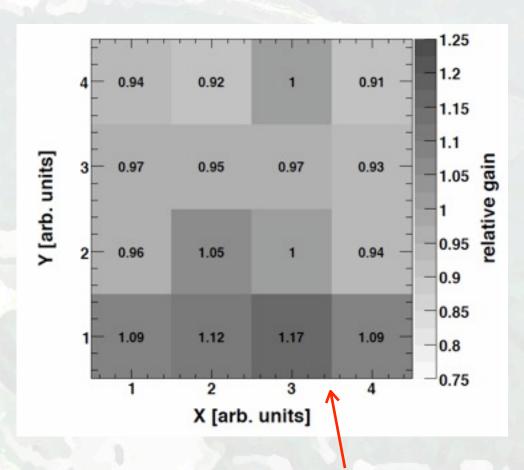


- Gain measured with low intensity ⁵⁵Fe source (~0.5Hz/mm²)
- Good gain uniformityover full active area(Measured after chargebuilt-up)



Source tests (3)



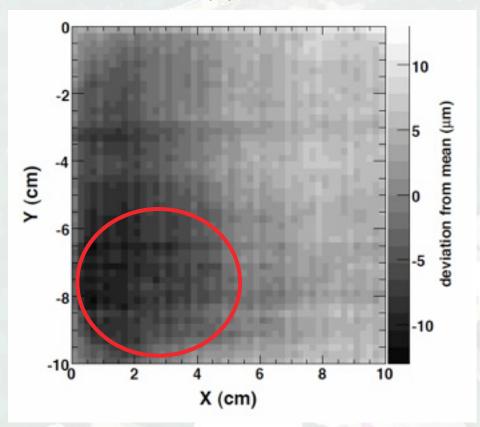


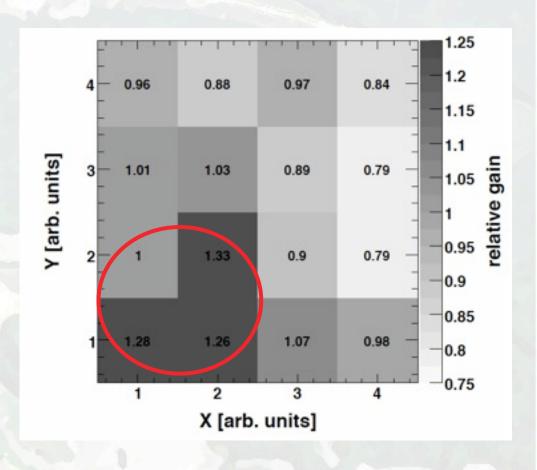
O Comparison of optical scans of inner hole diameter uniformity and gain uniformity

from low-intensity ⁵⁵Fe source (~0.5Hz/mm²) measurements



Source tests (4)



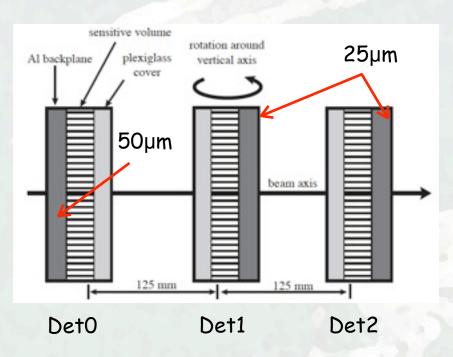


O Non-uniformity of inner hole diameter (~20µm smaller on left side compared to right side)

reflected in large non-uniformity of source scan gain measurements



Testbeam results (1)





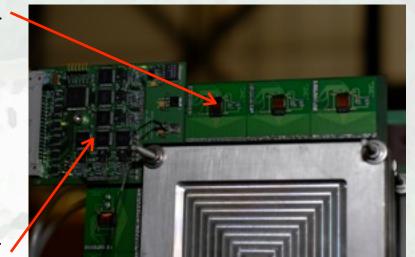
APV25-S1

O FNAL Meson Test Beam Facility: Data taking with

4GeV-32GeV unseparated secondary beam and

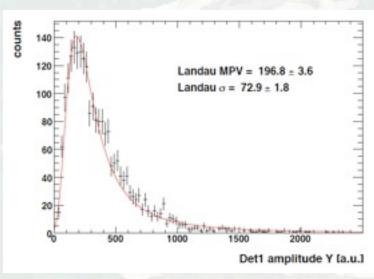
120GeV primary proton beam

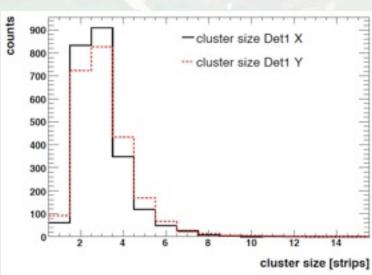
GEM Control Unit

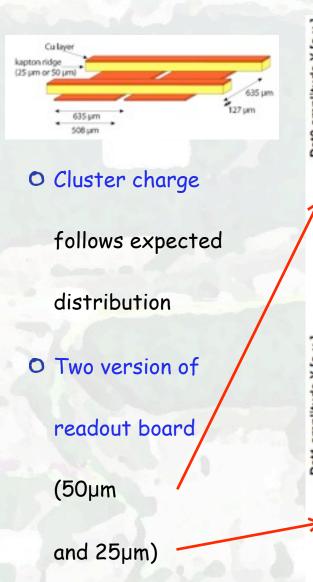


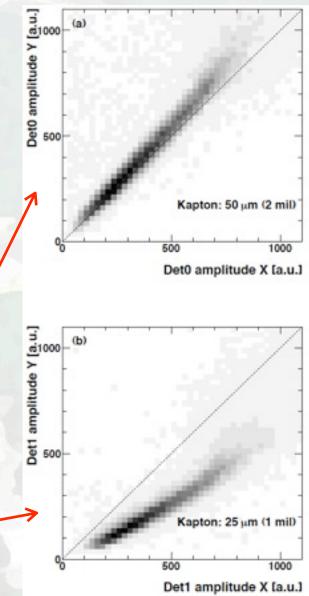


Testbeam results (2)



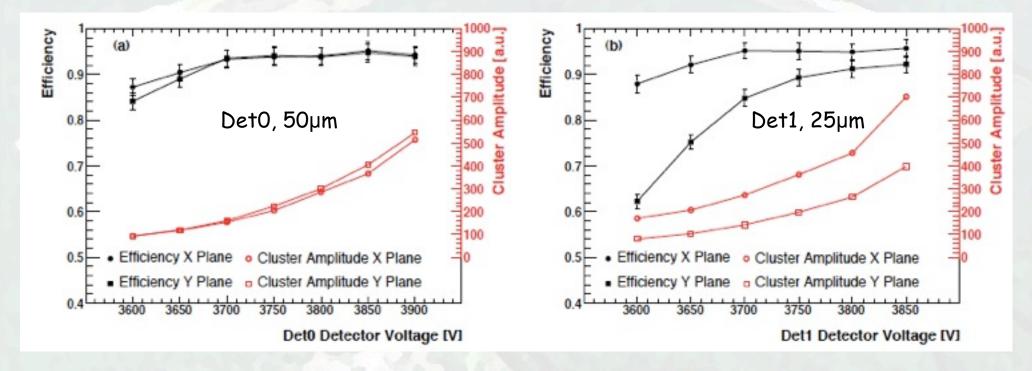








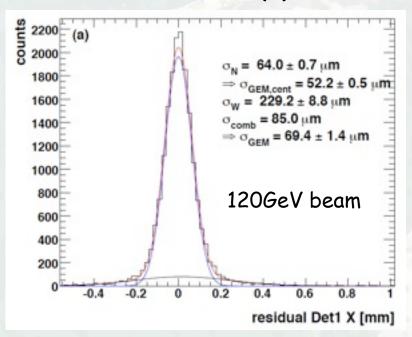
Testbeam results (3)

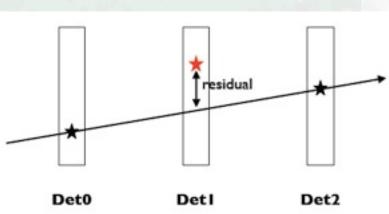


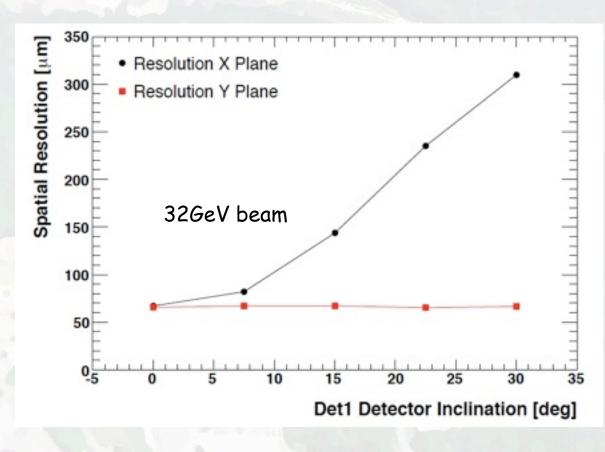
- Efficiencies at the level of ~95%-98% were reached in regions which limit the impact of noisy and dead regions with Tech-Etch GEM foils (Not affected by high intensity studies)
- O Clear difference between DetO (50µm) and Det 1 (25µm) for efficiency and cluster amplitude (Most probable value of Landau distribution)



Testbeam results (4)



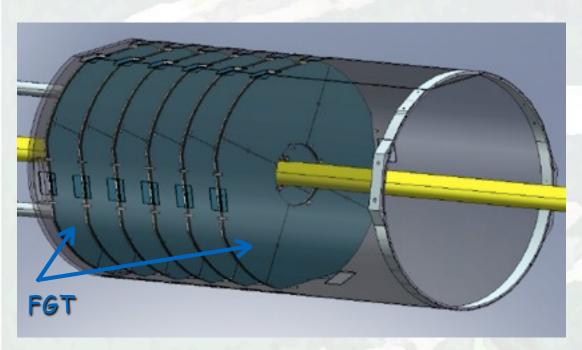


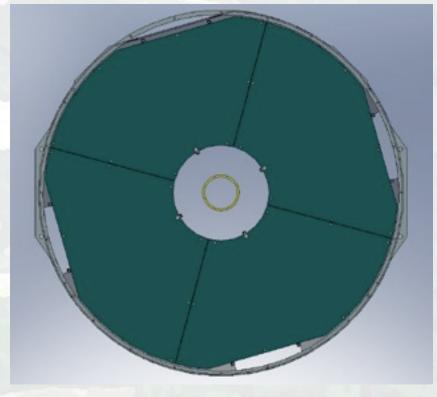


Study of inclination by up to 30°: Only X (horizontal) resolution is affected, not so for Y (vertical) coordinate as expected!



Layout



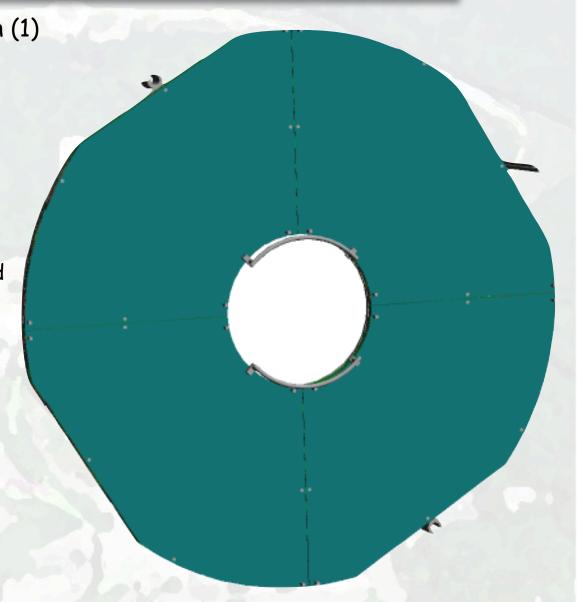


- FGT: 6 light-weight disks
- Each disk consists of 4 triple-GEM chambers (Quarter sections)

Procurement and assembly of full quarter section prototype in preparation

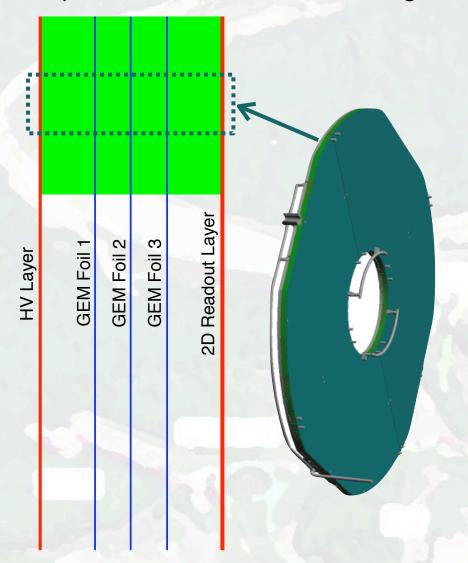


- Triple-GEM: Quarter section design (1)
 - Single disk
 - O 5mm Nomex honeycomb
 - O 0.25mm FR4 skins
 - O Pins used as part of assembly and alignment
 - GEM quadrant
 - O Pins define position
 - O Pins preserve shape
 - O Gas manifolds and rails





Triple-GEM: Quarter section design (2)



Component	Material	Radiation Length [%]
Support plate	5 mm Nomex	0.040
	2x250 μm FR4	0.257
HV layer	5 μm Cu	0.035
	50 μm Kapton	0.017
GEM foils	6x5 μm Cu (70%)	0.147
1	3x50 μm Kapton (70%)	0.036
Readout	5 μm Cu (20%)	0.007
	50 μm Kapton (20%)	0.003
	5 μm Cu (88%)	0.031
	50 μm Kapton	0.017
	5 μm Cu (10%)	0.004
	0.125 mm FR4	0.064
	5 μm Cu (10%)	0.004
Drift gas	10 mm CO ₂ (30%)	0.002
9	10 mm Ar (70%)	0.006
Total		0.670

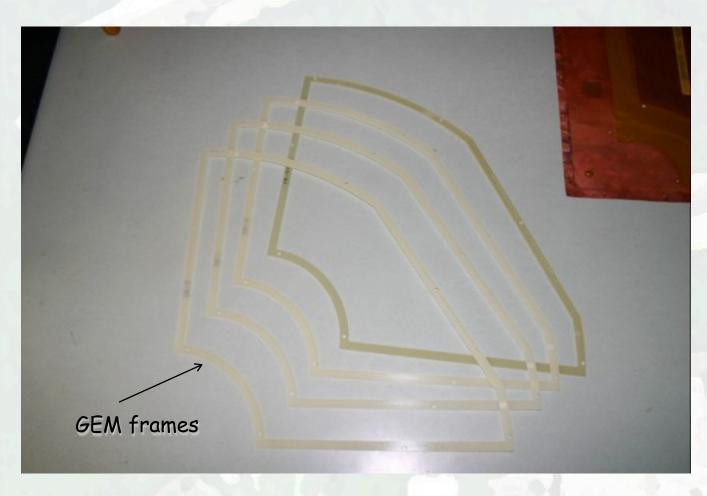


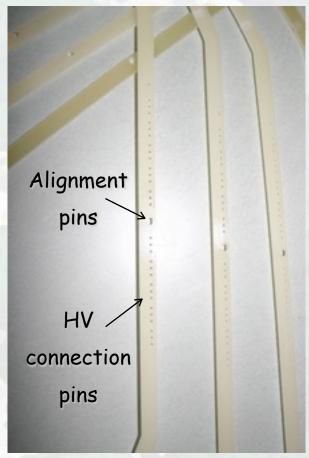
Triple-GEM: Quarter section design (3)

- 1cm wide frames of FR4
- 2-3mm thick
- Inner radius: 10.5cm
- Outer radius: 38.1cm
- O Flat at 31°
- 1mm gap between quadrants
- 4mm FR4 pins
- 34 X 1mm holes for HV GEM foil connection



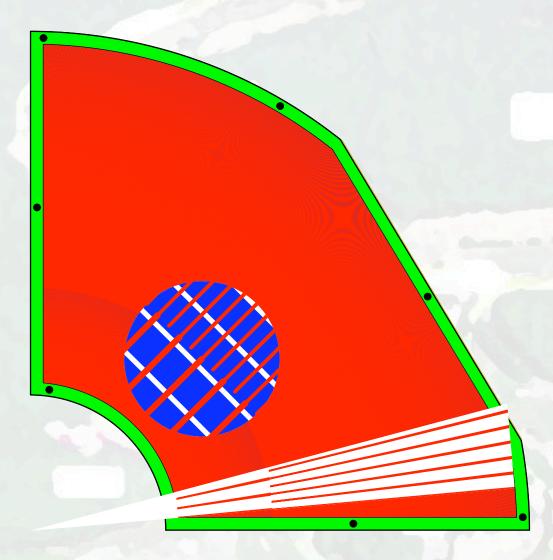
Triple-GEM: Quarter section design (4)







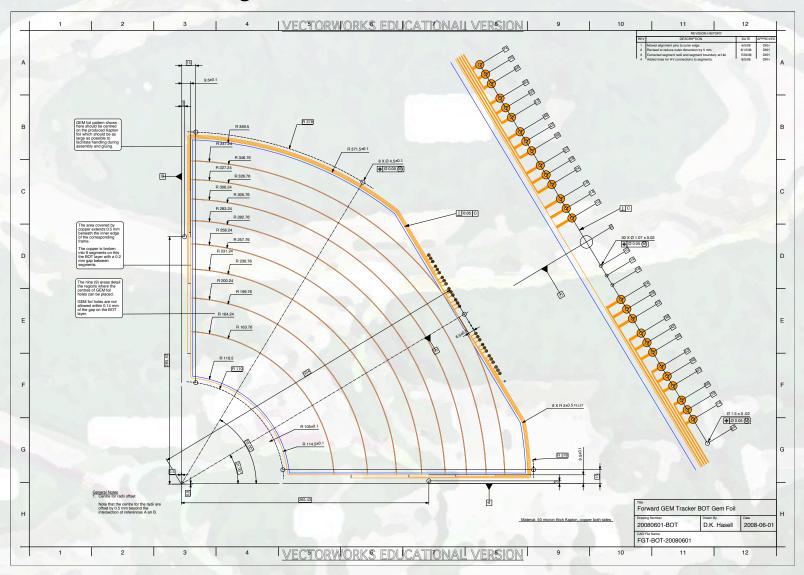
Triple-GEM: Quarter section design (5)



- O 50 μm Kapton
 - O Copper on both sides
 - O Laser etching exposes bottom layer
- Top layer
 - O Φ -readout layer
 - O Alternate lines end at 18.8cm
 - O Pitch: 300-600 μm
 - O Line width: 80-120µm
- Bottom layer
 - O R-readout layer
 - O Pitch: 800µm
 - O Line width: 700μm

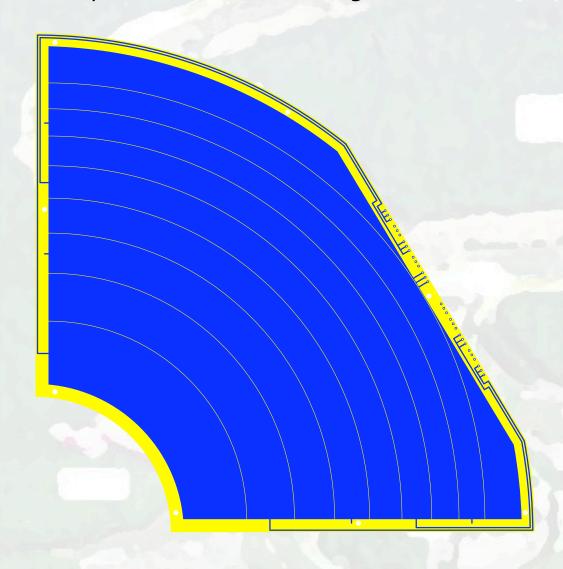


Triple-GEM: GEM foil design (1)





Triple-GEM: GEM foil design (2)



Segmented GEM foils:

- Minimize damage in case of breakdown
- 9 segments in radial direction
 with ~100cm² each
- O Gap: 200μm
- Hole pitch (~ 140μm) and
 diameter (I: ~50μm /O: ~60μm)
 similar to prototype!
- Routing and vias distribute HV to segments

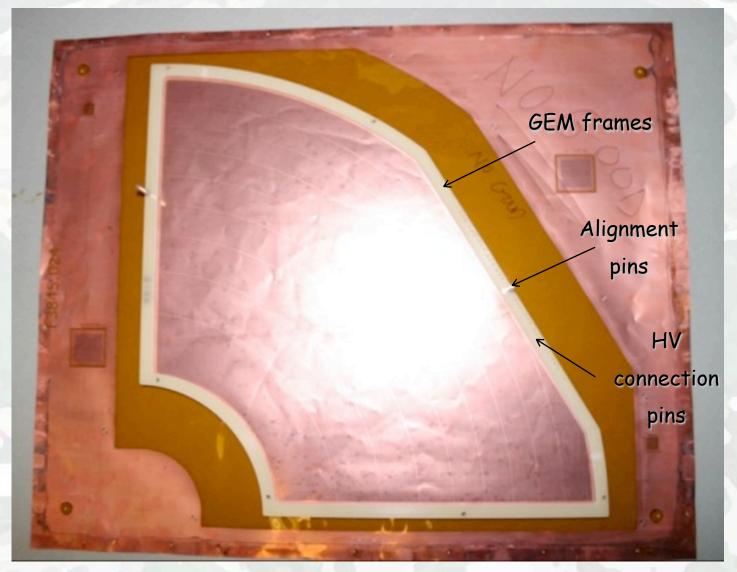


Triple-GEM: GEM foils at MIT (1)



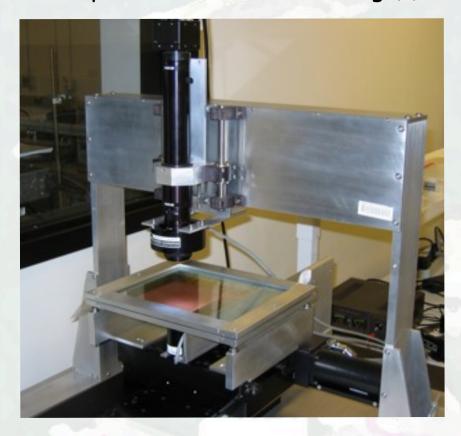


Triple-GEM: GEM foils at MIT (2)





Triple-GEM: GEM foil testing (1)





CCD camera setup for optical GEM foil scans

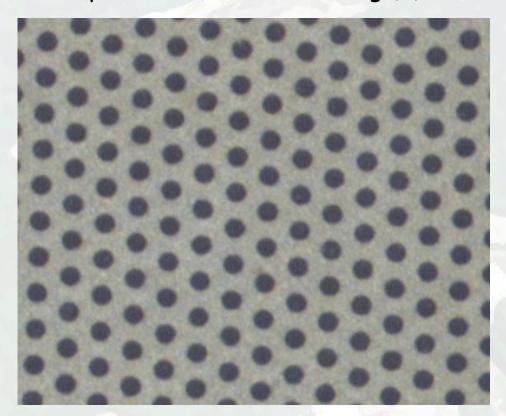
(Glass plate modifications in progress)

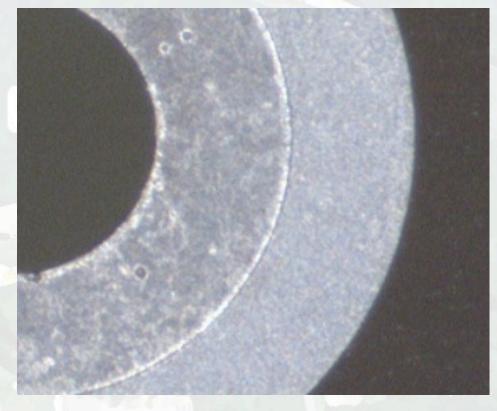
HV Vacuum / Nitrogen box for GEM foil dark current tests

(Minor modifications necessary - In progress)



Triple-GEM: GEM foil testing (2)



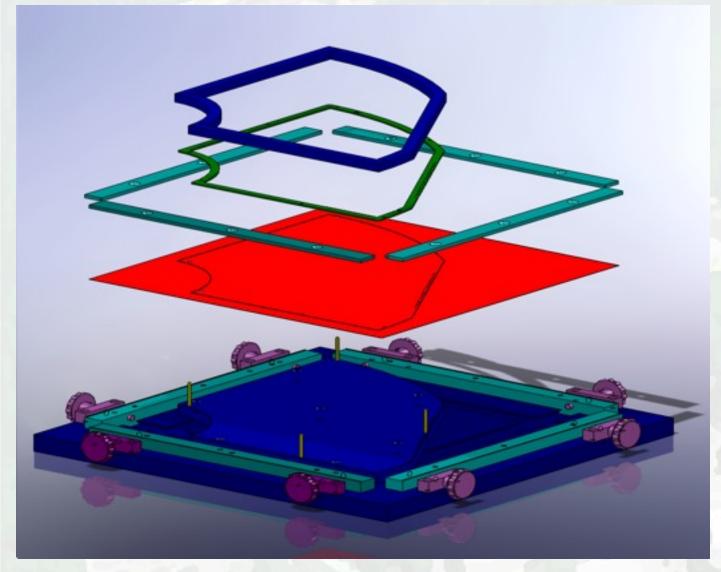


First scan for large GEM foil (Hole arrangement)

First scan for large GEM foil (HV connection)



Triple-GEM: GEM foil stretching and assembly tooling



Stretching jig:

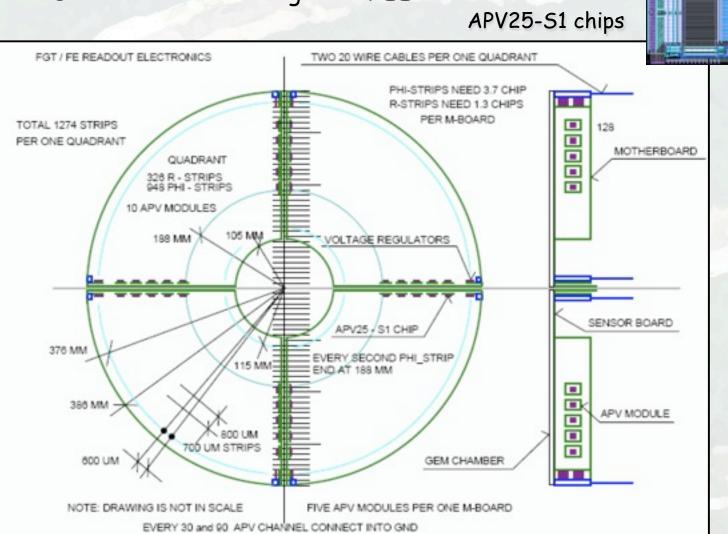
- Stretch GEM foil
- Clamp 2mm spacer for single glue operation

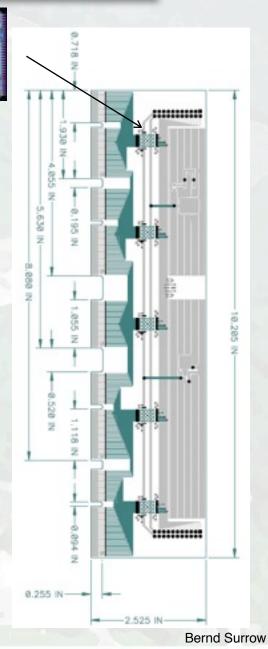
Assembly jig:

- Align frames to each other and to SIMM pins
- Hold frames flat with clamps
- Hold SIMM pins in place for soldering
- Clamp frames together for gluing operation



2D readout board design and FEE







Summary and Outlook

Summary

- Exciting program of W production in polarized proton-proton collisions at RHIC constraining unknown u/d anti-quark distributions
 Clear sensitivity in particular at forward rapidity
- STAR experiment requires upgrade of forward tracking system for charge sign discrimination of electrons/positrons
- Triple-GEM technology provides a cost effective way for a forward tracking upgrade solution
- Successful development of industrial production of GEM foils (SBIR proposal with Tech-Etch Inc.) Test of large GEM foils ongoing
- Successful beam test at FNAL demonstrates that performance meets requirements
- Design work being finalized Pre-production underway
- O Goal: Installation summer 2010 to be ready for Run 11

